

# Integrated Glass Substrates for Advanced Display and Electronic Applications

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## Abstract

*Engineered glass substrates optimized for material attributes, form factors, and innovative processing capabilities are crucial for emerging high-performance display and non-display applications. Through system-level optimization, these advanced substrates enable the heterogeneous assembly of electronic and opto-electronic devices supporting current applications, as well as, shaping the future technology roadmap.*

## Author Keywords

glass substrates; displays; electronics; opto-electronics; engineered substrates

Glass substrates are currently used for a wide variety of display and non-display applications. Engineered glass compositions and forming methods have been specifically optimized to enable innovative progress in active-matrix backplanes, display technologies, and mechanically durable cover glass. Similarly, glass wafers are being used for semiconductor device processing and packaging, including fan-out and 2.5D/3D packaging, wafer thinning, 3D bonding, and temporary carriers.[1] These display and non-display applications value a key set of glass intrinsic and extrinsic attributes, such as surface quality, low warp and Total Thickness Variation (TTV), optical performance, thermo-mechanical stability, thermal expansion, Young's modulus, hermeticity, and environmental durability. Optimized unique attribute sets for these applications have been scaled up to Gen10 glass sheets and 450 mm wafers.

Emerging high-performance display and non-display devices, however, require a new level of substrate integration. In addition to attributes that derived from the glass compositions and forming methods, new substrate and device processing capabilities are required. Beyond the now standard additive and subtractive processes, substrates must be designed for and truly enable heterogeneous assembly of hybrid electronic and opto-electronic devices. New assembly approaches such as pick-and-place and micro-transfer printing are being explored. This heterogeneous integration utilizes the optimal material for each

functionality and achieves new device designs, high-throughput manufacturing methods, and enhanced performance levels. Examples of these emerging applications include: microLED displays, micro-driver ICs, glass core, co-packaged optics, mmWave communication, die-embedded packaging, frequency-selective and refractive-impedance surfaces, foldable displays, LIDAR, as well as, lighting and photovoltaics.[2,-8] These emerging applications require the substrate to have a higher level of integration within the device design and functionality through its material attributes, form factor, and processing capability.

Substrate material attributes can be tailored over wide ranges to meet device and application requirements. As the degree of integration increases, a system-level optimization is required. The substrate is not a stand-alone element but is highly influential in the device and system performance. It should be noted that although glass is referred to, glass-ceramic and ceramic substrates may be the optimal material depending on the application. The substrate can also be comprised of laminates or multi-layers that include these material families. Identifying the correct substrate composition is a multi-parameter optimization. Table 1 illustrates example glass attribute ranges that different applications may value combinations of. By engaging in technically challenging research & development, glass scientists have often been able to balance many competing composition and manufacturing factors and exploit new and unexpected behaviors of glass materials to achieve desired substrate attributes. Similar to glass, ceramic substrates such as alumina are options that can achieve low RF loss ( $\sim 10^{-4}$ ), and high thermal conductivity ( $>36\text{W/mK}$ ) to enable high power electronics.[8]

Substrate form factors and processing capabilities are also critical for device integration. As mentioned, both wafer and sheet formats are possible, and thicknesses can range from  $<100\ \mu\text{m}$  to  $>2\ \text{mm}$ . Corning's advanced fusion forming capability provides as-formed surfaces with  $R_a$  roughness  $< 3\ \text{\AA}$ , TTV  $< 2\ \mu\text{m}$ , and panel warp  $\ll 500\ \mu\text{m}$ . [1] After forming, the substrate can be further processed to create device-level features

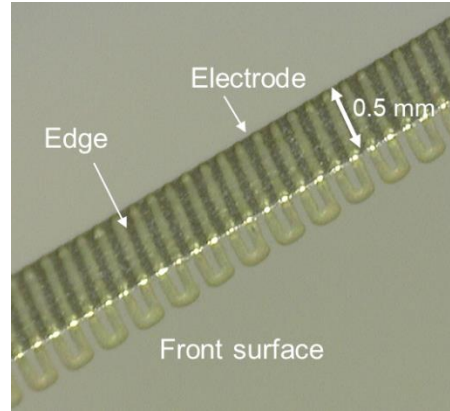
required for true integration. Examples of this include the formation of surface features, through-glass vias (TGV), ion-exchange for strengthening or waveguide formation, and laser-written waveguides.[1,8-12] Singulation after device fabrication is also critical [13], especially for applications such as tiled microLED displays that require precision sizes. Capabilities exist for precision cutting and edge finishing within 100 μm of device structures that have edge accuracy ~10 μm and chamfer widths <60 μm.[14]

**Table 1.** Glass substrate example attribute ranges.

<u>Attribute</u>	<u>Example ranges</u>
CTE	3-10 x 10 <sup>-6</sup> /°C
Youngs modulus	65-83 GPa
Dielectric constant and loss tangent (@ 10 GHz)	Dk: 4.6 – ~7 Df: 0.003 – 0.03
Optical transmission, UV cut-off (90% knee)	220-320 nm (320-420 nm)
Strain point	570-750°C
Refractive index (λ = 587 nm)	1.458-2.00

Devices can be fabricated and assembled on these engineered substrates using a variety of high-throughput sheet and wafer capabilities. In addition, carrier substrates and roll-to-roll processing can be utilized with flexible form factors.[8] Examples of device processing include: TGV metallization, redistribution layer (RDL) patterning with line/space dimensions < 5/5 μm, wrap-around electrode patterning (Figure 1) with lines/space dimensions down to 20 μm / 20 μm.[1,4,14-16] In terms of overall device integration, the substrate attributes, form factors, and process capabilities have been utilized in the heterogenous assembly of display and non-display applications with microLED, micro-IC, and Si die components.[2,17]

In summary, engineered glass substrates enable emerging high-performance display and non-display applications by optimizing material attributes, form factors, and innovative processing capabilities. A system-level approach is essential to optimize the specific attribute combinations required for targeted device designs, performance levels, and manufacturing processes. This optimization has enabled the heterogeneous assembly of electronic and opto-electronic integrated devices. These capabilities not only support current applications but also play a critical role in shaping the future technology roadmap.



**Figure 1.** Wrap-around electrode patterning of 50 μm lines and spaces for tiled and borderless displays. The glass substrate has a precision edge finish with a <60 μm chamfer.

**References**

- Lafosse X. (2024) Glass substrates for advanced packaging. International Semiconductor Executive Summits.
- Meitl M, et al., (2023) Emitters for flat panel microLED displays. SID Display Week.
- Logunov S, Kobayakov A, Xiao Y, Peters DR, Sauer M (2023) Reflector antennas based on flexible ceramic and glass substrates. 2023 IEEE Aerospace Conference, doi: 10.1109/AERO55745.2023.10115956
- Seok SH, et al., Advanced glass substrate fabrication and metallization process technology for Cu electrodes inside cavity and TGV (2024) IEEE EPTC
- Kang B, et al., (2021), 57-2: Glass-embedded Electromagnetic Surface for Energy-Saving Future Wireless Communication. SID Symposium Digest of Technical Papers, 52: 802-805. <https://doi.org/10.1002/sdtp.14805>
- Kang B, et al., (2023), 70-3: Tunability of Reconfigurable Intelligent Surface (RIS) using Liquid Crystal (LC) according to Various Bias Voltage Levels. SID Symposium Digest of Technical Papers, 54: 993-996. <https://doi.org/10.1002/sdtp.16735>
- Lee, C., Choi, H., Kang, B., Kang, B. and Huh, J. (2024), 18-2: A Novel Design for Reconfigurable Intelligent Surfaces (RIS) with Thin Liquid Crystal Layer for Wireless Communications. SID Symposium Digest of Technical Papers, 55: 208-211. <https://doi.org/10.1002/sdtp.17491>
- Garner S, et al., (2024) Flexible inorganic substrates for electronic device hybrid integration. IEEE IFETC.
- Brusberg L. et al., (2024) Photonic glass interposer with integrated optical waveguides for fiber-to-chip coupling. Photonics West.

10. Brusberg L, et al., (2023) Glass platform for co-packaged optics. *IEEE Journal of Selected Topics in Quantum Electronics*, doi: 10.1109/JSTQE.2023.3247245.
11. Huang S, Li M, Chen K (2017) Guided-wave photonics in flexible glass. In S.M. Garner (Ed.), *Flexible Glass: Enabling Thin, Lightweight, and Flexible Electronics* (pp.3-34). Hoboken, NJ: Wiley-Scrivener.
12. Huang S, et al., (2014) Ultrafast laser fabrication of 3D photonic components in flexible glasses. *Optical Fiber Communication Conference*.
13. Grenier JR, Brusberg L, Wieland KA, Matthies J and Terwilliger CC (2023) Ultrafast laser processing of glass waveguide substrates for multi-fiber connectivity in co-packaged optics. *Adv. Opt. Technol.* 12:1244009. doi: 10.3389/aot.2023.1244009
14. Pastel D, et al., Wrap-around electrodes for microLED tiled displays. *J Soc Inf Display*. 2020; 28: 463–468. <https://doi.org/10.1002/jsid.905>
15. Garner S, et al., (2022), 20-2: Integration of Through Glass Via Interconnects within Thin Film Transistor Active Matrix Backplanes. *SID Symposium Digest of Technical Papers*, 53: 218-220. <https://doi.org/10.1002/sdtp.15457>
16. Chang YH, et al., (2023) Wrap-around electrode fabrication via laser ablation. *SID IDW*
17. Okandan M, (2024) Flight Heritage, Radiation Recovery and Production Updates for DragonSCALES. 28th Space Photovoltaic Research and Technology Conference, Sept.4-6, 2024, NASA Glenn Research Center, Cleveland, OH